

Design and manufacturing of computer-generated holograms

Interferometric testing of aspheres and freeforms

Design and manufacturing of computer-generated holograms

Interferometric testing of aspheres and freeforms

Description

Computer-generated holograms (CGHs) allow for contact-free interferometric testing of demanding optical surfaces, for example aspheres or freeforms, with an accuracy < 10 nm RMS. To realize this, a high-precision lithographic fabrication technology and the use of special substrates with sub-100 nm flatness are needed.

Lithographic process chain

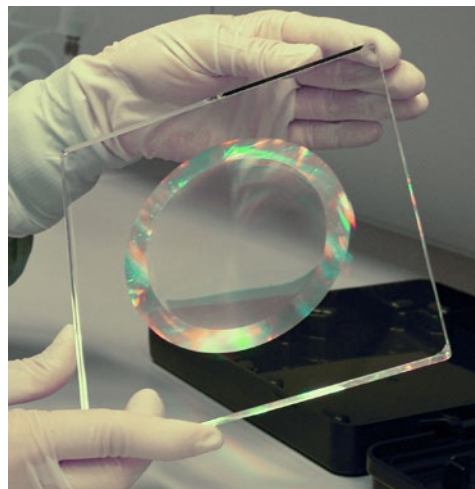
- Coating of substrate with chromium and photoresist
- Exposure by use of electron beam lithography
- Transfer of structure into chromium mask through reactive ion etching (RIE)
- Transfer of structure into substrate through RIE
- Removal of chromium mask (selective removal possible)

Technical data

- Available substrate geometries:
 - 6-inch (152 × 152 × 6.35) mm
 - 9-inch (230 × 230 × 9) mm
 - ET (292 × 150 × 15) mm
- Placement accuracy < 20 nm (3σ)

Our product range

- Optical design of phase functions and layout
- Provision and correction of substrates (transmitted wavefront error < 10 nm RMS)
- Lithographic fabrication of CGHs
- Measurement of placement accuracy
- Measurement of transmitted wavefront



Structured CGH on a 6-inch mask blank (152 mm × 152 mm × 6.35 mm).

Cover: Computer generated hologram on 6" fused-silica substrate.

Top: Interferometric testing of a freeform mirror pair using a specially designed CGH.

Contact

Department

Micro- and Nano-structured Optics

Head of Department

Dr. Falk Eilenberger

Phone +49 3641 807-274

falk.eilenberger@iof.fraunhofer.de

Scientific Group

Advanced Microoptical Components

Corona Schmalian

Phone +49 3641 807-751

corona.schmalian@iof.fraunhofer.de

Fraunhofer IOF

Albert-Einstein-Strasse 7

07745 Jena

Germany

www.iof.fraunhofer.de



scan for more info